

## PATENT ABSTRACTS OF JAPAN

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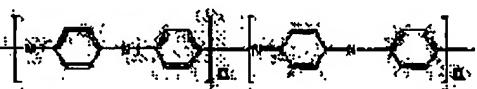
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## (54) FULLERENE-CONTAINING SENSITIVE MATERIAL, RESIST AND PATTERN FORMING METHOD USING SAME

## (57)Abstract:

**PROBLEM TO BE SOLVED:** To prevent the deterioration of the resist shape after exposure due to impurities in air by using a sensitive material comprising a substance having amino groups and a fullerene.  
**SOLUTION:** The sensitive material comprises a substance having amino groups and a fullerene or its derivative. The substance having amino groups is a polyaniline or its derivative. The fullerene or its derivative is not particularly limited but C<sub>60</sub> or its derivative having high reactivity with amino groups is preferably used. A polyaniline is desirably used as the substance having amino groups and a polyaniline having any unit cell such as aniline or aniline having a substituent may be used but a poly(o-alkylaniline) or a poly(o-alkoxyaniline) is preferably used in consideration of solubility to a solvent. The alkyl group in the poly (o-alkylaniline) has 1-24, more preferably 1-12 carbon atoms.



## EQUAL STATUS

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